

# ULTRARAM

ULTRA-EFFICIENT MEMORY

## AI-Native Memory Architecture

*Enabling Energy-Efficient AI Infrastructure*



James Ashforth-Pook

Co-founder & CEO - Quinas Technology Ltd.

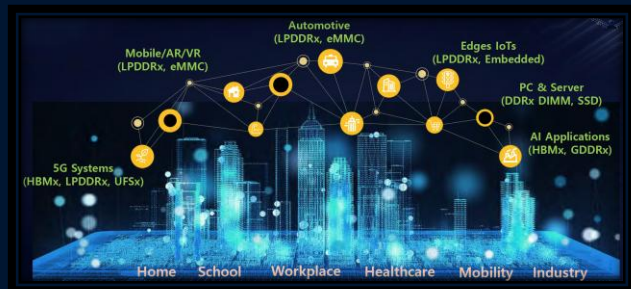
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# Explosive Data Growth Is Breaking the Memory Stack



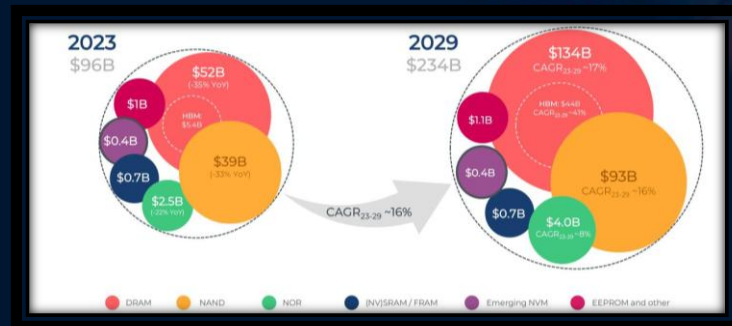
Explosive growth ahead:  
AI to drive \$1T market by 2030



Memory powers every sector –  
from edge to cloud

## A \$234B Global Memory Market (and Growing)

Including adjacent and emerging memory segments



Representative memory market leaders

Source: Yole (public market estimates)



South Korea



USA



Taiwan



Japan

AI scaling is now constrained by memory energy - not compute

ULTRARAM™ is uniquely positioned to meet this need

# Memory Scaling Has Structurally Failed

Why AI infrastructure urgently needs a new memory architecture

## Digital Energy Pressure

- Data centers consume 2–3% of global electricity
- Projected to double by 2030
- DRAM's constant power draw is a core inefficiency
- AI model training and inference are driving a step-change in memory-related energy demand

## Industry at a Scaling Wall

- Moore's Law and Denard Scaling are breaking down
- DRAM: fast but volatile and power-hungry
- NAND: non-volatile but slow, with limited endurance

## Performance vs. Power Trade-Off

AI, 5G/6G, and Edge workloads need memory that is:

- Fast, Non-volatile, and Energy-efficient
- No current memory tech achieves all three

## Market Gap = Investor Opportunity

- \$150B+ memory market is ripe for disruption
- Legacy memory can't meet sustainability goals
- A new memory class is needed to unlock growth

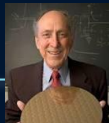
**ULTRARAM™ is designed to break the speed–power–volatility deadlock and redefine the future of memory.**

# ULTRARAM™: A Physics-Level Reset in Memory



1980


TOSHIBA



1966



Flash	DRAM
✗ High voltage switching (<20 V)	✓ Low voltage/energy switching (<2V)
✗ Intrinsically slow P/E (10 $\mu$ s)	✓ Fast operation (10 ns)
✗ Low endurance ( $10^5$ )	✓ High endurance ( $10^{16}$ )
✓ Non-volatile	✗ Volatile
✓ Non-destructive read	✗ Destructive read
✓ Highly scalable	✗ Scaling challenges

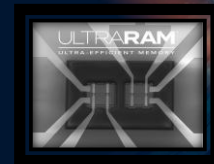


Flash is non-volatile, but slow and wears out...

DRAM is fast, but volatile and inefficient due to constant refreshing

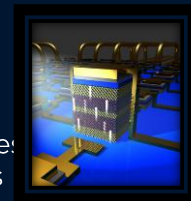
## What is the ULTRARAM™ Breakthrough

- A revolutionary universal memory combining:
  - Non-volatility of flash.
  - Speed and endurance beyond DRAM.



## Core Technology:

- Compound semiconductors replace silicon for enhanced performance. (InAs/GaSb-based quantum wells)
- Triple-barrier resonant tunneling (TBRT) eliminates refresh cycles, wear issues and drastically reduces power.



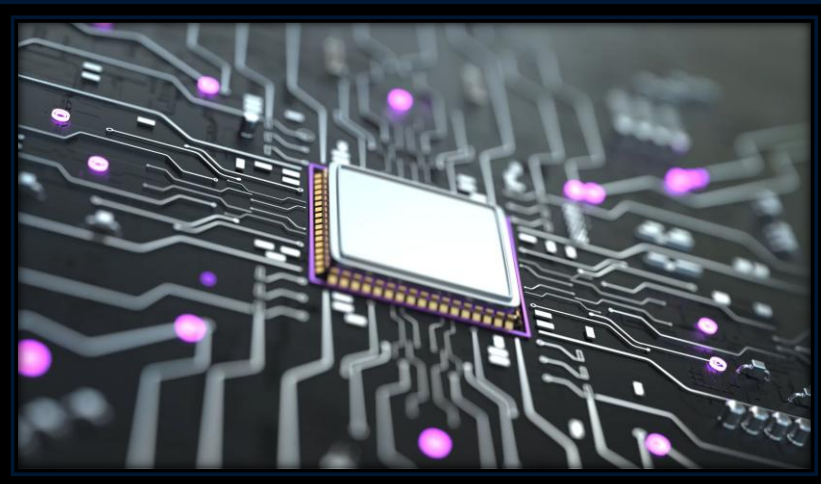
ULTRARAM™ is not a hybrid — it is a new device enabled by different physics

ULTRARAM™ delivers DRAM-class speed with non-volatile persistence — enabled by novel device physics.

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# The Physics Behind AI-Native Memory

Persistent, high-bandwidth, ultra-low power memory enabled by novel quantum resonant tunnelling physics



<https://bit.ly/ultraram>

ULTRARAM  
ULTRA-EFFICIENT MEMORY

# Why the Industry Wants a Universal Memory

Simplified – Energy Efficient - Scalable



## Collapse the Memory Hierarchy

One memory layer reducing reliance on SRAM, DRAM, Flash and HDD



## Future Architectures

Enables in-memory, neuromorphic, and chiplet system designs



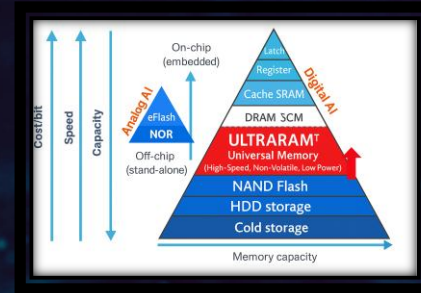
## Performance & Energy

Low-latency, high-speed memory with dramatically lower energy per operation



## Security

Enables secure architectures via controlled persistence, rapid zeroisation, and tamper-aware operation for trusted/encrypted compute..



*Universal Memory enables a new class of fast, persistent system memory*



## Speed + Non-Volatility

Fast, persistent system memory enabling new compute models



## Sustainability

Lower energy consumption and reduced system waste

# ULTRARAM™ Is Already De-Risked

## Patented Physics Breakthroughs:

- Anchored by our proprietary Triple Barrier Quantum Resonant Tunneling (**TBRT**) technology, enabling step-change improvements in energy efficiency and performance.
- Protected by multiple global patent families (5 awarded and 8 pending patents in 4 patent families, with a fifth disclosure pending) across the US, UK, Europe, Japan, South Korea, China.
- More than 10 years of R&D

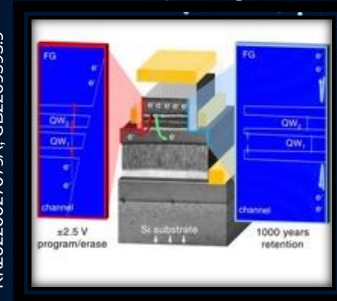
## Advanced Materials and Design:

- Incorporates compound semiconductors like **InAs, GaSb, and AISb** for unmatched endurance and efficiency.
- Scalable to silicon substrates, accelerating adoption.

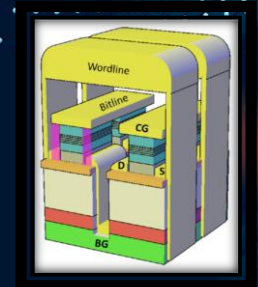
## Externally validated innovation:

- **Flash Memory Summit (FMS) 2023 USA.** - Most Innovative Startup
- **IC Taiwan Grand Challenge 2024.** – Global Winner
- **WIPO Global Awards 2025 Geneva** - Spinout Intellectual Property

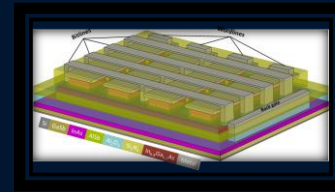
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Memory Device Physics

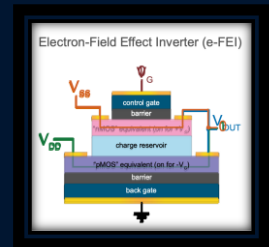


Scalable Bit Cell



Memory Array

16-bit RAM array design @ 4F2



Logic Device



# Step-Change Performance at the Device Level

## Performance Highlights:

- **Ultra-Low Switching Energy:** ~10 attojoules – per operation
  - (orders of magnitude lower than DRAM and NAND).
- **High Endurance:** Projected endurance >>10<sup>15</sup> cycles,
  - enabled by non-destructive, physics-based switching.
- **High Speed:** Sub-nanosecond to nanosecond-class switching,
  - competitive with DRAM.
- **Non-Volatility Data retention:** >10 years at elevated temperature,
  - with projected lifetime >1,000 years.
- **Wide Temperature Range:** Operational capability
  - from the lowest cryogenic temperatures up to 100°C.
- **Radiation Hardness:** Inherently radiation-tolerant device physics
  - for harsh environments (Testing TBA)

Parameter	DRAM	3D NAND	MRAM	ReRAM	PCRAM	ULTRARAM™	
Storage time	~60 ms	>10 years	>10 years	> 10 years	>10 years	>10 years	●
Non-destructive read?	No	Yes	Yes	Yes	Yes	Yes	●
Switching energy	1 fJ	~10 fJ	~100 fJ	~1,000 fJ	>1 pJ	~10 aJ <sup>(1)</sup>	●
Switching voltage	<1 V	>10 V	<1.5 V	<3 V	1-3 V	≤2.5 V	●
Energy barrier	0.5 eV	1.6 eV	1.5 eV	1.4 eV	2.4 eV	2.1 eV	●
Cell size	6F <sup>2</sup>	<<4F <sup>2</sup>	6F <sup>2</sup>	(4-12)F <sup>2</sup>	(4-30)F <sup>2</sup>	≤6F <sup>2</sup>	●
Switching time	10 ns	>10 ms	10-50 ns	10-100 ns	10-100 ns	~1 ns <sup>(1)</sup>	●
Endurance	10 <sup>6</sup>	10 <sup>5</sup>	10 <sup>12</sup>	Up to 10 <sup>12</sup>	Up to 10 <sup>12</sup>	>10 <sup>15</sup> <sup>(1)</sup>	●

**Energy Efficiency:** Significantly reduced power consumption for memory-intensive and AI workloads.



NV >1k yrs



Super Fast



High endurance



Low disturb



Ultra-efficient

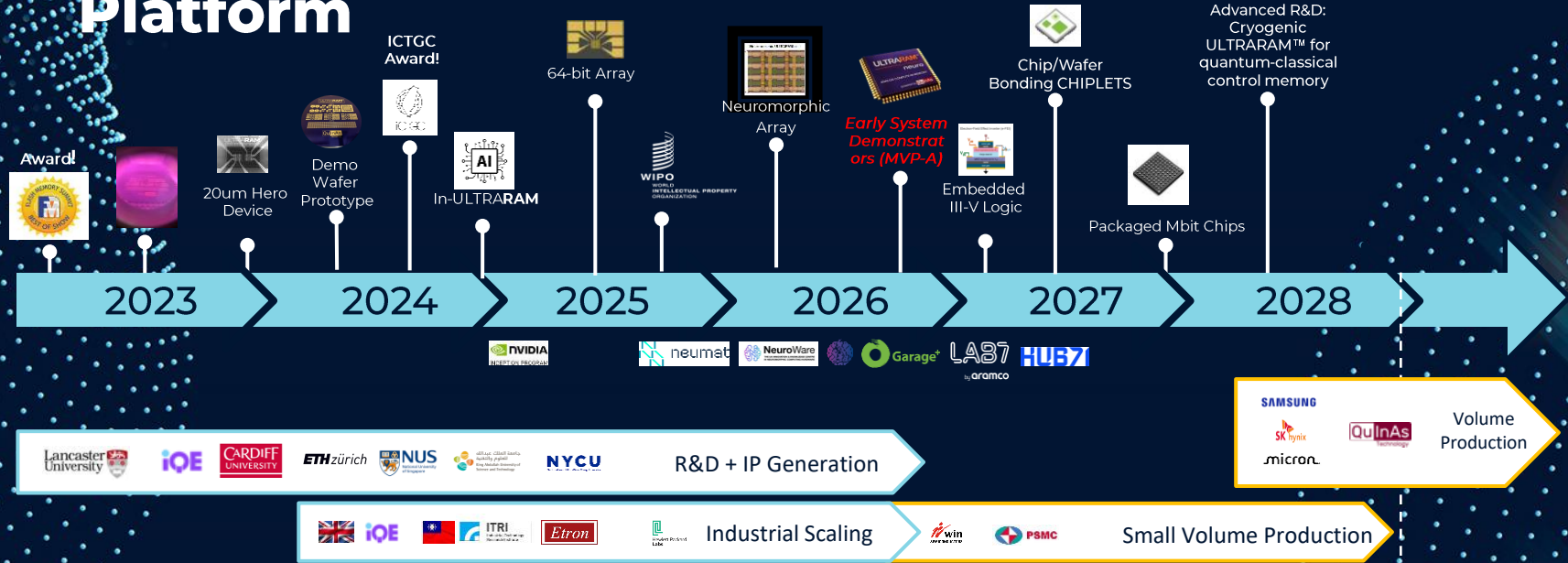


Wide temp range



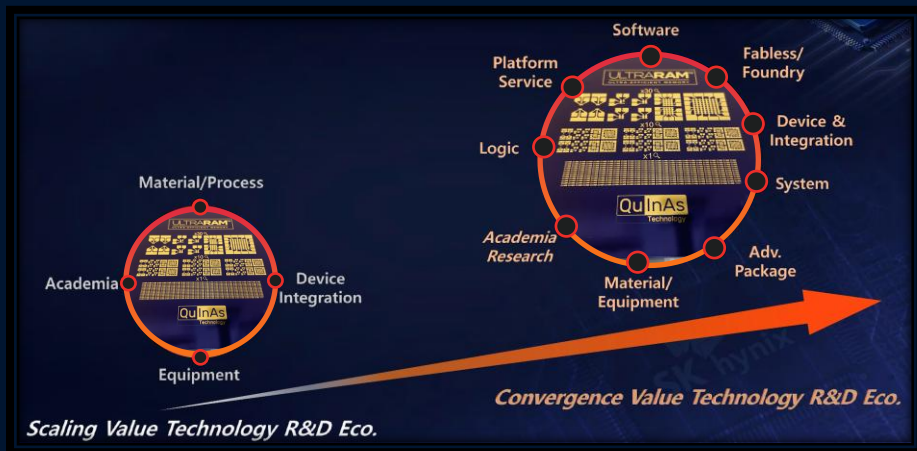
RadHard

# From Breakthrough Device to AI-Native Memory Platform



- **2026–2027: Platform Validation & Initial Commercialisation**  
Pilot-scale arrays, MVP-A system demonstrators, early adopter deployments, and small-volume production.
- **2028+: Platform Scaling & Market Expansion**  
Packaged memory products, advanced chiplet integration, and volume adoption across telecoms, datacentres, and IoT.

# Execution Through a Convergent Semiconductor Ecosystem



- End-to-end coverage: materials, epitaxy, devices, packaging, and system integration
- Parallel progress: physics, manufacturing, and applications developed concurrently
- De-risked scale-up: early alignment with industrial fabrication and packaging partners

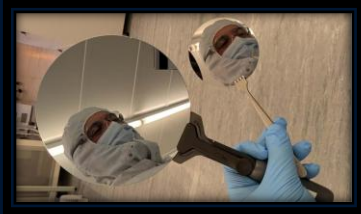


ULTRARAM™ development is embedded across materials, devices, systems, and manufacturing — reducing execution and scale-up risk.

# Full-Stack Partnerships for ULTRARAM™ Scale-Up

Covers the full stack from materials → AI System Validation → manufacturing

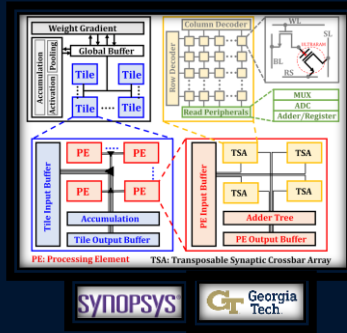
## Materials & Epitaxy



### Industrial Epitaxy & Materials Platform

- Transition from MBE → industrial MOCVD (IQE)
- ULTRARAM™ demonstrated on 6" GaSb wafers
- Compatible with III-V manufacturing workflows

## AI System Validation



### Device & System-Level Validation

- Physics-based ULTRARAM™ models (IIT Roorkee)
- Integrated into Synopsys design flows
- System-level validation via NeuroSim (Georgia Tech)

## Manufacturing Readiness

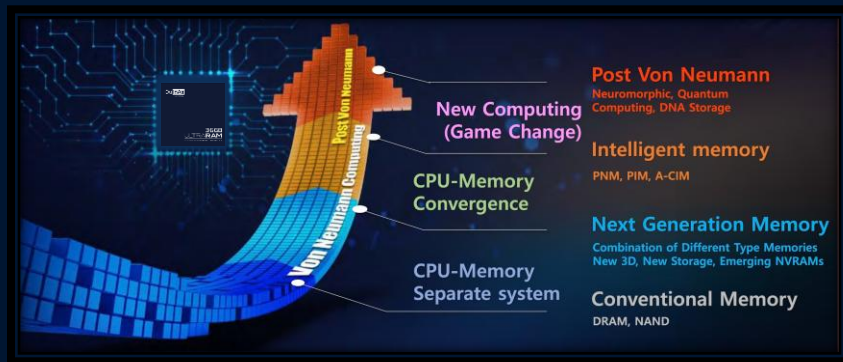


### Fabrication Readiness

- Atomic Layer Etching (ALE) quantum-well precision
- Oxford Instruments + LayTec process control
- Enables repeatable, scalable fabrication

*De-risks ULTRARAM™ from lab-scale innovation to foundry-scale semiconductor production*

# ULTRARAM™ Anchors the Next Memory Paradigm







- The memory wall has shifted from bandwidth to energy, latency, and data movement.
- HBM solves bandwidth but exposes system-level power and cost limits.
- Persistent, compute-adjacent memory is required to collapse the memory hierarchy and reduce data movement.

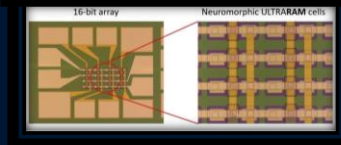
*ULTRARAM™ enables this convergence by combining speed, persistence, and ultra-low energy at the device level.*

# First Physics-Validated ULTRARAM™ Compute-in-Memory Demonstration MVP-A

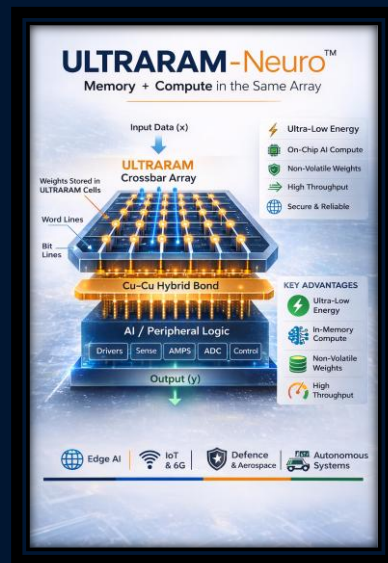
## MVP-A Validates:

- \* ULTRARAM™ device physics integrated into compute architecture
- \* Analog MAC operations using multi-level memory states
- \* System-level performance via NeuroSim (Georgia Tech)
- \* Measurable energy & density advantages vs CMOS systems

Literature	Die Layout	Type	Efficiency (TOPS/W)	Density (TOPS/mm <sup>2</sup> )	Array Size	ADC Type
BM LABS		RRAM-CMOS	30 (8 levels)	0.29	128X128X2	TDC
ULTRARAM		Floating Gate	80 (32 Levels)	~0.29 (6F2)	Development	TDC
NVIDIA H100		Full-CMOS	9.36	0.04 (400F2)	-	-
Google TPU v1		Full-CMOS	2.3	0.06	-	SAR



DiRac Lab  
ECE, 117, Room 400



De-risks ULTRARAM™ as a viable compute-in-memory platform for AI hardware..

# Outperforming DDR5 in Power, Performance & Potential – MVP-D

System-level persistent memory that reduces HBM power, capacity, and cost pressure in AI data centres



## Why ULTRARAM™ Stands Out:

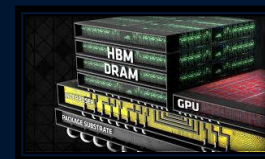
Combines DRAM-class speed with non-volatile persistence to enable HBM-efficient system architectures.

**Sustainable:** Eliminates refresh and reduces memory energy per inference and training step — directly addressing AI data-centre power and cooling limits. Reducing AI infrastructure energy intensity at system level.

**Scalable:** Designed for seamless integration into existing global memory manufacturing and packaging systems.

**Reliable:** Long retention, high endurance, and radiation resistance for mission-critical use cases.

**Future Proof:** Positioned for future computing paradigms, including AI, neuromorphic and the secure quantum-era systems.



Validated by ETH Zurich SAFARI Group

**Modelling predicts disruptive gains in efficiency and scalability.**

# Early Adopters, Beachhead & Expansion Markets

## PRIMARY BEACHHEAD — MVP-A First, MVP-D Follow-on

### MVP-A — AI & Edge Computing (Neuromorphic / In-Memory Compute)

- Collapses memory and compute for AI-native architectures
- Exploits speed, non-volatility, and ultra-low energy.
- First MVP to validate the platform and unlock scale



### MVP-D — Digital Persistent Memory (DRAM-Class)

- Addresses digital memory systems requiring speed + persistence
- Natural progression toward DRAM-adjacent systems
- Leverages the same ULTRARAM™ device platform

MVP-A is the first commercial platform, enabled by the same ULTRARAM™ device foundation that later scales into system memory MVP-D



### EARLY ADOPTERS — Validation & De-Risking

Space, Defence & Quantum

- Radiation-tolerant, non-volatile memory for extreme environments
- Early adoption driven by physics advantages, not cost
- Initial deployments, qualification, and market credibility

### EXPANSION MARKETS — Post-MVP-A Scale

- Data Centres — Persistent system memory and energy savings
- Telecoms (5G/6G) — Low-latency, energy-efficient infrastructure
- Automotive / Industrial / IoT — Reliability and endurance and temperature resilience



# Team

## Founder team



**James Ashforth-Pook**  
CEO

38+ years in semiconductors and high-growth global startups / scale-ups. Commercialisation & global partnerships



**Prof Manus Hayne**

CSO  
inventor of ULTRARAM™ (device physics and architecture) 35+ years experience.



**Dr Peter Hodgson**  
CTO

Expertise in semiconductor materials with 15+ years experience in III-V devices process integration & manufacturability



## Research Team



**Dr Serdar Tekin**  
Postdoc (arrays)



**Kacper Burczyk**  
PhD\* (scaling)



**Bianca Giuroiu**  
PhD (logic)

## External Tech advisors



**Dr J. Iwan Davies**  
Grp Tech Dir, IQE PLC



**Prof Avirup Dasgupta**  
Indian Institute of Tech Roorkee



**Prof Kwon Kee-Won**  
Sung Kyun Kwan University



**Prof Dr Onur Mutlu**  
Full Professor, Dept. Information Tech and Elec. Eng.



# Global Validation & Momentum

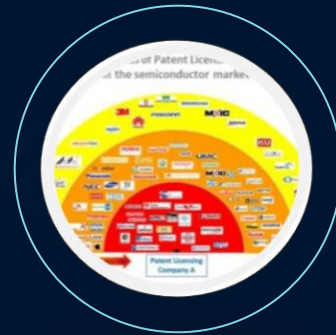
- **£5m+ non-dilutive** funding secured, validating ULTRARAM™ across UK and international programmes
- **Lead partner** in Innovate UK's flagship memory programme, alongside IQE and Cardiff University
- **ICTGC Winner (Taiwan, 2024)** — selected from leading global semiconductor startups
- **WIPO Global Awards recognition** for ULTRARAM™ intellectual property
- **First strategic investor secured in South Korea (2025)**
- **Active global collaborations spanning the UK, Europe, Taiwan, Korea, and Singapore** (IQE, Lancaster, ETH Zürich, NUS, KAUST)

*Government, industry, and investor engagement across the UK, Taiwan, India, South Korea:*

*This momentum underpins our transition from publicly funded validation to private capital scale-up.*



# Business Model - Fabless, Licensing-Led Memory Platform



**Innovation**

**Industrialise**

**License**

**Scale**

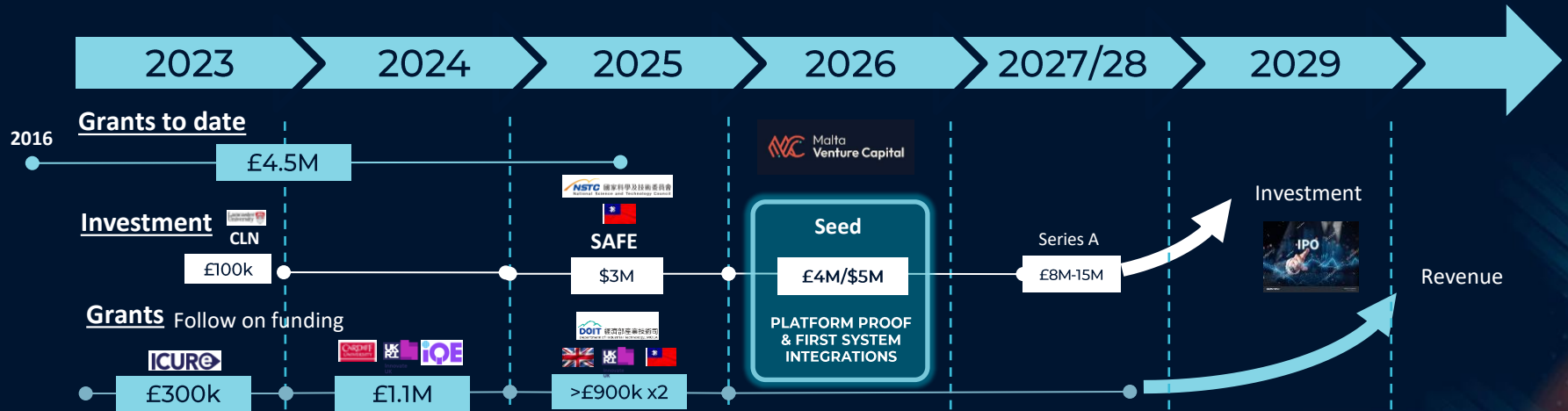
## Revenue Streams:

- IP Licensing & Royalties
- Strategic co-development
- AI memory chiplets & packaged devices
- Defence & AI infrastructure applications

## Scaling Strategy:

- Partner-led manufacturing & packaging
- Semiconductor ecosystem integration
- Capital-efficient scale-up through global foundry and packaging partners

# Funding Roadmap



## Seed Execution Focus (18–24 Months):

- TRL-5→6 completion
- MVP-A system demos
- First manufacturing integrations (fables).

## What this round unlocks:

- MVP-A system demos with lead partners
- Foundry & package alignment for MVP-D
- Advanced packaging & chiplet integration

*Seed capital converts deep, publicly funded validation into platform revenue and scale*

## Delivers:

- A partner-ready **ULTRARAM™ MVP-A** for neuromorphic and in-memory AI compute
- **System-level proof of ultra-low-energy AI workloads**
- **A manufacturable path to scale with industry partners**

*18-24 month execution → Series A readiness*

**ULTRARAM™**  
ULTRA-EFFICIENT MEMORY





## HQ UK

- IP
- Commercial
- Partnerships

Great Portland St. London W1W 5PF



## R&D Labs UK

- Device Physics
- Pathfinding & Arrays

LU Physics, Lancaster LA1 4YB



## Taiwan

- Foundry
- Pilot Production
- Adv. Packaging

Taipei Arena 105037



## Malta EU

Valletta Europe



- EU Entity
- Incentive
- Structuring

Contact: ULTRARAM™ overview



*Quinas operates a distributed, fabless model optimised for capital efficiency, speed, and global scale.*